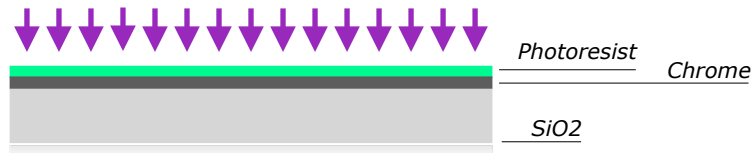


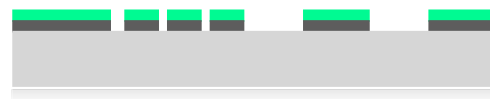
Conventional Photomask Process



1 *Pattern Exposure*



2 *Develop Resist*



3 *Wet etch chrome*



4 *Strip resist*